In the Claims:

Please cancel claims 3 and 6-14, without prejudice, amend claims 1, 4, and 15-16, and add new claims 17-20 as follows:

1. (Currently amended) A texturing apparatus for a recording medium substrate, comprising:

a rotational spindle supported for rotation in an attitude perpendicular to a predetermined datum plane;

a contact member supported for movement in a radial direction of the rotational spindle along the datum plane;~~-and~~

a drive connected to the rotational spindle ~~so as to vary a rotation rate of the rotational spindle in response to movement of the contact member~~and varying a rotation rate of the rotational spindle;

an urging force adjuster connected to the contact member and applying an urging force to the contact member toward a surface of the recording medium substrate; and

a controller connected to the drive and the urging force adjuster and controlling the drive and the urging force adjuster so that a ratio between a relative velocity and the urging force of the contact member is maintained constant,

wherein the relative velocity is defined between the contact member and the surface of the recording medium substrate.

2. (Original) The texturing apparatus according to claim 1, further comprising a vibrator connected to the contact member so as to reciprocate the contact member by a predetermined amplitude along the radial direction.

3. (Cancelled)

4. (Currently amended) A method of texturing a substrate for a recording medium, comprising:

~~contacting~~applying an urging force to a contact member ~~against~~toward a surface of the substrate of a disk-shape rotating around a rotational spindle;

moving the contact member in a radial direction of the substrate; and

~~varying a rotation rate of the substrate around the rotational spindle in accordance with movement of the contact member~~maintaining a predetermined ratio between a relative velocity and the urging force of the contact member,

wherein the relative velocity is defined between the contact member and the surface of the substrate.

5. (Original) The method of texturing according to claim 4, further comprising reciprocating the contact member in contact with the substrate by a predetermined amplitude along the radial direction.

6-14. (Cancelled)

15. (Currently amended) An apparatus designed to texture a substrate of a recording medium, comprising:

a rotational spindle supported for rotation in an attitude perpendicular to a predetermined datum plane, said rotational spindle receiving the substrate;

a contact member supported for movement in a radial direction of the rotational spindle along the datum plane; and

a drive connected to the rotational spindle so as to vary a rotation rate of the rotational spindle in response to movement of the contact member,

wherein the movement of the contact member causes a texture spreading over a surface of the substrate.

16. (Currently amended) The apparatus according to claim 15, wherein ~~said substrate has no magnetic film thereon~~ the texture comprises stripes of fine scratches, and a cross angle is defined between intersecting ones of the stripes of fine scratches.

17. (New) The texture apparatus according to claim 1, further comprising a supply unit supplying the contact member with abrasive liquid including abrasive grains.

18. (New) The texture apparatus according to claim 1, wherein the controller controls the drive and the urging force adjuster according to

$(h/R) = (4.89\eta u)/(w/L)$ wherein,

h denotes a thickness of the abrasive liquid between the contact member and the substrate, R denotes a radius of the contact member, η denotes a viscosity of the abrasive liquid, u denotes the relative velocity, w denotes the urging force of the contact member, and L denotes a length of a linear contact between the contact member and the substrate.

19. (New) The method of texturing according to claim 4, further comprising the step of supplying the contact member with an abrasive liquid having abrasive grains.

20. (New) The method according to claim 19, wherein a relative velocity u between the contact member and the substrate is determined according to

$(h/R) = (4.89\eta u)/(w/L)$ wherein,

h denotes a thickness of the abrasive liquid between the contact member and the substrate, R denotes a radius of the contact member, η denotes a viscosity of the abrasive liquid, u denotes the relative velocity, w denotes the urging force of the contact member, and L denotes a length of a linear contact between the contact member and the substrate.